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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/766,212	01/29/2004	Masaru Takaishi	AI 325	3347

7590 07/26/2005
RABIN & BERDO, P.C.
1101 14 Street, N.W., Suite 500
Washington, DC 20005

EXAMINER

TOLEDO, FERNANDO L

ART UNIT	PAPER NUMBER
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2823

DATE MAILED: 07/26/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

10/766,212

Applicant(s)

TAKAISHI, MASARU

Examiner

Fernando L. Toledo

Art Unit

2823

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 29 January 2004.
- 2a) ☐ This action is FINAL. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-9 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1-9 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☒ The specification is objected to by the Examiner.
- 10) ☒ The drawing(s) filed on 29 January 2004 is/are: a) ☒ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☒ All b) ☐ Some * c) ☐ None of:
1. ☒ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) ☒ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☒ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date 1/29/04, 4/23/04, 6/29/05
- 4) ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____
- 5) ☐ Notice of Informal Patent Application (PTO-152)
- 6) ☐ Other: _____

DETAILED ACTION

Specification

1. The title of the invention is not descriptive. A new title is required that is clearly indicative of the invention to which the claims are directed.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

3. Claims 1 – 9 are rejected under 35 U.S.C. 102(b) as being anticipated by Hsu et al. (U. S. Patent 6,143,645 A).
4. In re claim 1, Hsu, in the U. S. Patent 6,143,645 A; figures 1 – 3 and related text, discloses forming a silicon-containing thin film 500 in a region having a predetermined area including the inner surface of the contact hole on the surface of the semiconductor substrate; forming an aluminum-containing thin film 520 on the surface of the semiconductor substrate on which the silicon-containing thin film is formed; and heating the semiconductor substrate on which the aluminum-containing thin film is formed to such a temperature as to cause silicon to diffuse with respect to aluminum (Column 4, Lines 15 – 30 and Figure 3).
5. In re claim 2, Hsu discloses wherein the step of forming an aluminum-containing thin film and the step of heating the semiconductor substrate is carried out simultaneously (Column 4, Lines 15 – 30).

6. In re claim 3, Hsu discloses wherein the step of heating the semiconductor substrate is carried out after completing the step of forming an aluminum-containing thin film (Figure 3).

7. In re claim 4, Hsu discloses wherein the step of forming a silicon-containing thin film in the region having the predetermined area includes the step of: forming a silicon-containing thin film in a region larger than the predetermined area; and removing the silicon-containing thin film so that the area of the silicon-containing thin film can become the abovementioned predetermined area (Column 7, Lines 16 – 19).

8. In re claim 5, Hsu discloses wherein the step of removing the silicon-containing thin film includes a step of removing the silicon-containing thin film using a mask having a predetermined pattern (it is conventional in the art that to form a plug a mask must be used to avoid etching the plug).

9. In re claim 6, Hsu discloses wherein the step of removing the silicon-containing thin film includes a step of removing the silicon-containing thin film by etching (it is well-known in the art and conventional to remove unwanted portions by etching).

10. In re claim 7, Hsu discloses wherein the predetermined area is not more than 99% of the area of the aluminum-containing thin film formed in the step of forming the aluminum thin film (Figure 2).

11. In re claim 8, Hsu discloses wherein the semiconductor substrate is provided with several cells each including the contact hole, and the ratio of the amount of silicon contained in the silicon-containing thin film formed in the region having the predetermined area per unit cell to the amount of aluminum supplied to a unit cell in the step of forming the aluminum thin film is not less than 0.1% and not more than 2% by atomic ratio (Figure 3).

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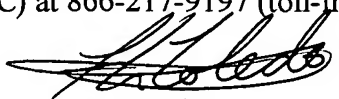
12. In re claim 9, Hsu discloses wherein the step of heating the semiconductor substrate includes a step of heating the semiconductor substrate to 380°C – 570°C (Column 4, Lines 15 – 30).

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Fernando L. Toledo whose telephone number is 571-272-1867. The examiner can normally be reached on Mon-Thu 7am to 5:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



Fernando L. Toledo
Examiner
Art Unit 2823

flt
23 July 2005